Jindrich Musil

List of Publications by Year in Descending Order

289 papers	9,923 citations	49 h-index	89 g-index
299 ext. papers	10,601 ext. citations	3.4 avg, IF	6.52 L-index

#	Paper	IF	Citations
289	Surface processes on KBr single crystals examined by thermostimulated exo-electron emission and desorption. *Optical Materials*, **2021**, 114, 110898	3.3	2
288	Hard alloy films with enhanced resistance to cracking. *Vacuum*, **2021**, 188, 110186	3.7	2
287	Simultaneous measurements of thermostimulated exo-electron emission, luminescence, and desorption from a KBr single crystal. *Optical Materials*, **2020**, 109, 110223	3.3	3
286	THERMAL STABILITY OF HARD TANTALUM BORIDE FILMS. *High Temperature Material Processes*, **2020**, 24, 193-200	1.8	2
285	Superhard metallic coatings. *Materials Letters*, **2019**, 247, 32-35	3.3	2
284	Flexible hard (Zr, Si) alloy films prepared by magnetron sputtering. *Thin Solid Films*, **2019**, 688, 137216	2.2	6
283	Coating of overstoichiometric transition metal nitrides (TMNx (x > 1)) by magnetron sputtering. *Japanese Journal of Applied Physics*, **2019**, 58, SAAD10	1.4	1
282	Tribological properties and oxidation resistance of tungsten and tungsten nitride films at temperatures up to 500 °C. *Tribology International*, **2019**, 132, 211-220	4.9	8
281	Interrelationships among macrostress, microstructure and mechanical behavior of sputtered hard Ti(Al,V)N films. *Materials Letters*, **2019**, 235, 92-96	3.3	4
280	□(Me1, Me2) and MeNx films deposited by magnetron sputtering: Novel heterostructural alloy and compound films. *Surface and Coatings Technology*, **2018**, 337, 75-81	4.4	12
279	Hard TiN2 dinitride films prepared by magnetron sputtering. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2018**, 36, 040602	2.9	4
278	Effect of intense electron and ion irradiation on optical absorption of boron carbide thin films. *Radiation Effects and Defects in Solids*, **2018**, 173, 1075-1082	0.9	3
277	Effect of energy on macrostress in Ti(Al,V)N films prepared by magnetron sputtering. *Vacuum*, **2018**, 158, 52-59	3.7	6
276	Irradiation of sputtered Al-Si-N coatings by pulsed 200 keV C+ ion beam. *Vacuum*, **2018**, 158, 65-67	3.7	6
275	(Zr,Ti,O) alloy films with enhanced hardness and resistance to cracking prepared by magnetron sputtering. *Surface and Coatings Technology*, **2017**, 322, 86-91	4.4	8
274	Evolution of microstructure and macrostress in sputtered hard Ti(Al,V)N films with increasing energy delivered during their growth by bombarding ions. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2017**, 35, 020601	2.9	19
273	Flexible Antibacterial Coatings. *Molecules*, **2017**, 22,	4.8	17

272	Plasma and floating potentials in magnetron discharges. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2017**, 35, 060605	2.9	4
271	Effect of energy on structure, microstructure and mechanical properties of hard Ti(Al,V)Nx films prepared by magnetron sputtering. *Surface and Coatings Technology*, **2017**, 332, 190-197	4.4	19
270	Creation and behavior of radicals and ions in the Acetylene/Argon microwave ECR discharge. *Plasma Processes and Polymers*, **2017**, 14, 1700062	3.4	
269	Mass spectrometry investigation of magnetron sputtering discharges. *Vacuum*, **2017**, 143, 438-443	3.7	7
268	Flexible hard Al-Si-N films for high temperature operation. *Surface and Coatings Technology*, **2016**, 307, 1112-1118	4.4	26
267	Protection of brittle film against cracking. *Applied Surface Science*, **2016**, 370, 306-311	6.7	13
266	A Detailed Investigation of Radicals and Ions in ECR Methane/Argon Microwave Discharge. *Plasma Processes and Polymers*, **2016**, 13, 970-980	3.4	2
265	Flexible antibacterial Zr-Cu-N thin films resistant to cracking. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2016**, 34, 021508	2.9	12
264	Flexible hydrophobic ZrN nitride films. *Vacuum*, **2016**, 131, 34-38	3.7	20
263	Effect of energy on the formation of flexible hard Al-Si-N films prepared by magnetron sputtering. *Vacuum*, **2016**, 133, 43-45	3.7	15
262	Flexible hard nanocomposite coatings. *RSC Advances*, **2015**, 5, 60482-60495	3.7	130
261	Mechanical characterization of a-C:H:SiOx coatings synthesized using radio-frequency plasma-assisted chemical vapor deposition method. *Thin Solid Films*, **2015**, 590, 299-305	2.2	39
260	Flexible antibacterial AlCuN films. *Surface and Coatings Technology*, **2015**, 264, 114-120	4.4	14
259	Thermal stability and transformation phenomena in magnetron sputtered AlCuO films. *Ceramics International*, **2015**, 41, 6020-6029	5.1	3
258	Contamination of Magnetron Sputtered Metallic Films by Oxygen From Residual Atmosphere in Deposition Chamber. *Plasma Processes and Polymers*, **2015**, 12, 416-421	3.4	22
257	Protective over-layer coating preventing cracking of thin films deposited on flexible substrates. *Surface and Coatings Technology*, **2014**, 240, 275-280	4.4	22
256	Mechanical and tribological properties of Sn-Cu-O films prepared by reactive magnetron sputtering. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2014**, 32, 021504	2.9	1
255	Thermally activated transformations in metastable alumina coatings prepared by magnetron sputtering. *Surface and Coatings Technology*, **2014**, 240, 7-13	4.4	14

254	Hard Nanocomposite Coatings **2014**, 325-353		13
253	Hydrophobicity of Thin Films of Compounds of Low-Electronegativity Metals. *Journal of the American Ceramic Society*, **2014**, 97, 2713-2717	3.8	51
252	Mass Spectrometric Characterizations of Ions Generated in RF Magnetron Discharges during Sputtering of Silver in Ne, Ar, Kr an.d Xe Gases. *Plasma Processes and Polymers*, **2013**, 10, 593-602	3.4	7
251	RF magnetron sputtering of silver thin film in Ne, Ar and Kr discharges: plasma characterisation and surface morphology. *Surface and Coatings Technology*, **2013**, 228, S466-S469	4.4	20
250	Nucleation of ultrathin silver layer by magnetron sputtering in Ar/N2 plasma. *Surface and Coatings Technology*, **2013**, 228, S86-S90	4.4	23
249	Mechanical and tribological properties of sputtered Mo□□N coatings. *Surface and Coatings Technology*, **2013**, 215, 386-392	4.4	8
248	Antibacterial Cr□Cu□ films prepared by reactive magnetron sputtering. *Applied Surface Science*, **2013**, 276, 660-666	6.7	20
247	High-rate pulsed reactive magnetron sputtering of oxide nanocomposite coatings. *Vacuum*, **2013**, 87, 96-102	3.7	21
246	Transparent Zr-Al□ oxide coatings with enhanced resistance to cracking. *Surface and Coatings Technology*, **2012**, 206, 2105-2109	4.4	42
245	Two-phase single layer Al-O-N nanocomposite films with enhanced resistance to cracking. *Surface and Coatings Technology*, **2012**, 206, 4230-4234	4.4	34
244	Hard nanocomposite coatings: Thermal stability, oxidation resistance and toughness. *Surface and Coatings Technology*, **2012**, 207, 50-65	4.4	454
243	The effect of addition of Al in ZrO2 thin film on its resistance to cracking. *Surface and Coatings Technology*, **2012**, 207, 355-360	4.4	28
242	Properties of nanocrystalline Al□Cu□ films reactively sputtered by DC pulse dual magnetron. *Applied Surface Science*, **2011**, 258, 1762-1767	6.7	32
241	Effect of nitrogen on tribological properties of amorphous carbon films alloyed with titanium. *Surface and Coatings Technology*, **2011**, 205, S84-S88	4.4	11
240	Investigation of the Negative Ions in Ar/O2 Plasma of Magnetron Sputtering Discharge with Al:Zn Target by Ion Mass Spectrometry. *Plasma Processes and Polymers*, **2011**, 8, 459-464	3.4	15
239	Elimination of Arcing in Reactive Sputtering of Al2O3 Thin Films Prepared by DC Pulse Single Magnetron. *Plasma Processes and Polymers*, **2011**, 8, 500-504	3.4	5
238	Comparison of hydrophilic properties of TiO2 thin films prepared by sol□gel method and reactive magnetron sputtering system. *Thin Solid Films*, **2011**, 519, 6944-6950	2.2	38
237	Tribological and mechanical properties of nanocrystalline-TiC/a-C nanocomposite thin films. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2010**, 28, 244-249	2.9	99

236	Two-functional DC sputtered Cu-containing TiO2 thin films. *Journal of Photochemistry and Photobiology A: Chemistry*, **2010**, 209, 158-162	4.7	19
235	In-situ X-ray diffraction studies of time and thickness dependence of crystallization of amorphous TiO2 thin films and stress evolution. *Thin Solid Films*, **2010**, 519, 1649-1654	2.2	20
234	High-rate reactive deposition of transparent SiO2 films containing low amount of Zr from molten magnetron target. *Thin Solid Films*, **2010**, 519, 775-777	2.2	27
233	Coefficient of friction and wear of sputtered a-C thin coatings containing Mo. *Surface and Coatings Technology*, **2010**, 205, 1486-1490	4.4	10
232	Thermal stability of alumina thin films containing □Al2O3 phase prepared by reactive magnetron sputtering. *Applied Surface Science*, **2010**, 257, 1058-1062	6.7	96
231	Generation of Positive and Negative Oxygen Ions in Magnetron Discharge During Reactive Sputtering of Alumina. *Plasma Processes and Polymers*, **2010**, 7, 910-914	3.4	15
230	Protective Zr-containing SiO2 coatings resistant to thermal cycling in air up to 1400 □C. *Surface and Coatings Technology*, **2009**, 203, 1502-1507	4.4	11
229	Two-Functional Direct Current Sputtered Silver-Containing Titanium Dioxide Thin Films. *Nanoscale Research Letters*, **2009**, 4, 313-320	5	19
228	Plasma Drift in Dual Magnetron Discharge. *IEEE Transactions on Plasma Science*, **2008**, 36, 1412-1413	1.3	14
227	Relationship between mechanical properties and coefficient of friction of sputtered a-C/Cu composite thin films. *Diamond and Related Materials*, **2008**, 17, 1905-1911	3.5	35
226	Hard amorphous nanocomposite coatings with oxidation resistance above 1000□C. *Advances in Applied Ceramics*, **2008**, 107, 148-154	2.3	61
225	Nanostructure of photocatalytic TiO2 films sputtered at temperatures below 200□C. *Applied Surface Science*, **2008**, 254, 3793-3800	6.7	51
224	Properties of magnetron sputtered Al□Si□N thin films with a low and high Si content. *Surface and Coatings Technology*, **2008**, 202, 3485-3493	4.4	48
223	Formation of crystalline Al□Ti□O thin films and their properties. *Surface and Coatings Technology*, **2008**, 202, 6064-6069	4.4	16
222	Role of energy in low-temperature high-rate formation of hydrophilic TiO2 thin films using pulsed magnetron sputtering. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2007**, 25, 666-674	2.9	65
221	Toughness of hard nanostructured ceramic thin films. *Surface and Coatings Technology*, **2007**, 201, 5148-5152	4.4	258
220	Novel model for film growth based on surface temperature developing during magnetron sputtering. *Surface and Coatings Technology*, **2007**, 202, 486-493	4.4	15
219	Atmospheric-Pressure Glow Discharge CVD of Composite Metallic Aluminium Thin Films. *Plasma Processes and Polymers*, **2007**, 4, 537-547	3.4	7

218	Effect of Al Addition on Structure and Properties of Sputtered TiC Films. *Plasma Processes and Polymers*, **2007**, 4, S6-S10	3.4	13
217	Effect of Hydrogen on Reactive Sputtering of Transparent Oxide Films. *Plasma Processes and Polymers*, **2007**, 4, S319-S324	3.4	6
216	Surface Morphology of Magnetron Sputtered TiO2 Films. *Plasma Processes and Polymers*, **2007**, 4, S345-S349	3.4	11
215	Photoactivated Properties of TiO2 Films Prepared by Magnetron Sputtering. *Plasma Processes and Polymers*, **2007**, 4, S531-S535	3.4	8
214	Oxidation of Sputtered Cu, Zr, ZrCu, ZrO2, and Zr-Cu-O Films during Thermal Annealing in Flowing Air. *Plasma Processes and Polymers*, **2007**, 4, S536-S540	3.4	4
213	Ti-Si-N Films with a High Content of Si. *Plasma Processes and Polymers*, **2007**, 4, S574-S578	3.4	18
212	High-rate low-temperature dc pulsed magnetron sputtering of photocatalytic TiO2films: the effect of repetition frequency. *Nanoscale Research Letters*, **2007**, 2, 123-9	5	20
211	Hard a-Si3N4/MeNx Nanocomposite Coatings with High Thermal Stability and High Oxidation Resistance. *Solid State Phenomena*, **2007**, 127, 31-36	0.4	34
210	PROPERTIES OF HARD NANOCOMPOSITE THIN FILMS **2007**, 281-328		9
209	High-power pulsed sputtering using a magnetron with enhanced plasma confinement. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2007**, 25, 42-47	2.9	71
208	Ion flux characteristics in high-power pulsed magnetron sputtering discharges. *Europhysics Letters*, **2007**, 77, 45002	1.6	55
207	Evolution of film temperature during magnetron sputtering. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2006**, 24, 1083-1090	2.9	24
206	Physical and Mechanical Properties of Hard Nanocomposite Films Prepared by Reactive Magnetron Sputtering. *Nanostructure Science and Technology*, **2006**, 407-463	0.9	20
205	Low-temperature sputtering of crystalline TiO2 films. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2006**, 24, 521-528	2.9	91
204	Magnetron Discharges for Thin Films Plasma Processing **2006**, 67-110		12
203	Difference in high-temperature oxidation resistance of amorphous ZrSiN and WSiN films with a high Si content. *Applied Surface Science*, **2006**, 252, 8319-8325	6.7	35
202	Properties of reactively sputtered WSiN films. *Surface and Coatings Technology*, **2006**, 200, 3886-3895	4.4	47
201	High-temperature oxidation resistance of TaSiN films with a high Si content. *Surface and Coatings Technology*, **2006**, 200, 4091-4096	4.4	38

200	Effect of addition of Cu into ZrOx film on its properties. *Surface and Coatings Technology*, **2006**, 200, 6792-6800	4.4	38
199	Enhanced hardness in sputtered ZrNiN films. *Surface and Coatings Technology*, **2006**, 200, 6293-6297	4.4	28
198	Thermal stability of magnetron sputtered ZrSiN films. *Surface and Coatings Technology*, **2006**, 201, 3368-3376	4.4	34
197	Control of macrostress in reactively sputtered MoAlN films by total gas pressure. *Vacuum*, **2006**, 80, 588-592	3.7	14
196	Magnetron sputtering of TiOxNy films. *Vacuum*, **2006**, 81, 285-290	3.7	41
195	Structure and mechanical properties of DC magnetron sputtered TiC/Cu films. *Vacuum*, **2006**, 81, 531-538	3.7	45
194	Discharge in dual magnetron sputtering system. *IEEE Transactions on Plasma Science*, **2005**, 33, 338-339	1.3	36
193	The Role of Energy in Formation of Sputtered Nanocomposite Films. *Materials Science Forum*, **2005**, 502, 291-296	0.4	21
192	NANOCOMPOSITE COATINGS WITH ENHANCED HARDNESS **2005**, 345-356		2
191	Reactive magnetron sputtering of thin films: present status and trends. *Thin Solid Films*, **2005**, 475, 208-218	2.2	276
190	Structure and properties of magnetron sputtered ZrSiN films with a high (25 at.%) Si content. *Thin Solid Films*, **2005**, 478, 238-247	2.2	51
189	Reactive magnetron sputtering of TiOx films. *Surface and Coatings Technology*, **2005**, 193, 107-111	4.4	60
188	Synthesis of TiO2 photocatalyst and study on their improvement technology of photocatalytic activity. *Surface and Coatings Technology*, **2005**, 200, 534-538	4.4	12
187	Optical emission spectra and ion energy distribution functions in TiN deposition process by reactive pulsed magnetron sputtering. *Surface and Coatings Technology*, **2005**, 200, 835-840	4.4	14
186	A study on the energy distribution for grid-assisting magnetron sputtering. *Surface and Coatings Technology*, **2005**, 200, 421-424	4.4	3
185	Physical properties and high-temperature oxidation resistance of sputtered Si3N4/MoNx nanocomposite coatings. *Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena*, **2005**, 23, 1568		32
184	Physical and mechanical properties of sputtered TaSiN films with a high (?40 at %) content of Si. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2004**, 22, 646	2.9	31
183	Pulsed dc Magnetron Discharges and their Utilization in Plasma Surface Engineering. *Contributions To Plasma Physics*, **2004**, 44, 426-436	1.4	98

182	Effect of ion bombardment on properties of hard reactively sputtered Ti(Fe)Nx films. *Surface and Coatings Technology*, **2004**, 177-178, 289-298	4.4	40
181	Hard Nanocomposite Films Prepared by Reactive Magnetron Sputtering **2004**, 43-56		3
180	Thermal annealing of sputtered AlSiCuN films. *Vacuum*, **2003**, 72, 21-28	3.7	12
179	Structure and mechanical properties of magnetron sputtered ZrTiCuN films. *Surface and Coatings Technology*, **2003**, 166, 243-253	4.4	51
178	Low-stress superhard Ti?B films prepared by magnetron sputtering. *Surface and Coatings Technology*, **2003**, 174-175, 744-753	4.4	85
177	Structure?property relationships in single- and dual-phase nanocrystalline hard coatings. *Surface and Coatings Technology*, **2003**, 174-175, 725-731	4.4	120
176	Measurement of hardness of superhard films by microindentation. *Materials Science & Engineering A: Structural Materials: Properties, Microstructure and Processing*, **2003**, 340, 281-285	5.3	31
175	Structure-hardness relations in sputtered TiAlYN films. *Thin Solid Films*, **2003**, 444, 189-198	2.2	45
174	Tribological Property of CeO2Films Prepared by Ion-Beam-Assisted Deposition. *Japanese Journal of Applied Physics*, **2003**, 42, 634-639	1.4	7
173	Thermal stability of PVD hard coatings. *Vacuum*, **2003**, 71, 279-284	3.7	105
172	Relationships between hardness, Young?s modulus and elastic recovery in hard nanocomposite coatings. *Surface and Coatings Technology*, **2002**, 154, 304-313	4.4	484
171	Effective nitriding of steels outside low-pressure microwave discharges. *Surface and Coatings Technology*, **2002**, 156, 182-184	4.4	1
170	The depth profile analysis of W-Si-N coatings after thermal annealing. *Surface and Coatings Technology*, **2002**, 161, 111-119	4.4	17
169	Composition, structure, microhardness and residual stress of WTiN films deposited by reactive magnetron sputtering. *Thin Solid Films*, **2002**, 408, 136-147	2.2	54
168	Relationship between structure and mechanical properties in hard AlSiCuN films prepared by magnetron sputtering. *Thin Solid Films*, **2002**, 413, 121-130	2.2	15
167	A comparative study on reactive and non-reactive unbalanced magnetron sputter deposition of TiN coatings. *Thin Solid Films*, **2002**, 415, 151-159	2.2	168
166	Morphology and Microstructure of Hard and Superhard ZrCuN Nanocomposite Coatings. *Japanese Journal of Applied Physics*, **2002**, 41, 6529-6533	1.4	21
165	Hard Nanocomposite Coatings Prepared by Magnetron Sputtering. *Key Engineering Materials*, **2002**, 230-232, 613-622	0.4	20

164	Hard and superhard ZrNiN nanocomposite films. *Surface and Coatings Technology*, **2001**, 139, 101-109	4.4	109
163	Magnetron sputtering of hard nanocomposite coatings and their properties. *Surface and Coatings Technology*, **2001**, 142-144, 557-566	4.4	183
162	Hard and superhard nanocomposite AlCuN films prepared by magnetron sputtering. *Surface and Coatings Technology*, **2001**, 142-144, 603-609	4.4	31
161	Magnetron sputtered Cr?Ni?N and Ti?Mo?N films: comparison of mechanical properties. *Surface and Coatings Technology*, **2001**, 142-144, 146-151	4.4	71
160	Control of structure in magnetron sputtered thin films. *Surface and Coatings Technology*, **2001**, 142-144, 201-205	4.4	9
159	Magnetron with gas injection through hollow cathodes machined in sputtered target. *Surface and Coatings Technology*, **2001**, 148, 296-304	4.4	7
158	Some growth peculiarities of a-C:H films in ECR microwave plasma. *Vacuum*, **2001**, 60, 315-323	3.7	5
157	The effect of Al composition on the microstructure and mechanical properties of WCTiAlN superhard composite coating. *Surface and Coatings Technology*, **2001**, 142-144, 596-602	4.4	23
156	Pulsed dc magnetron discharge for high-rate sputtering of thin films. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2001**, 19, 420-424	2.9	60
155	Recent progress in plasma nitriding. *Vacuum*, **2000**, 59, 940-951	3.7	29
154	Superhard nanocomposite Ti1AlxN films prepared by magnetron sputtering. *Thin Solid Films*, **2000**, 365, 104-109	2.2	228
153	Structure and properties of hard and superhard ZrCuN nanocomposite coatings. *Materials Science & Engineering A: Structural Materials: Properties, Microstructure and Processing*, **2000**, 289, 189-197	5.3	123
152	Hard nanocomposite ZrYN coatings, correlation between hardness and structure. *Surface and Coatings Technology*, **2000**, 127, 99-106	4.4	80
151	Hard and superhard nanocomposite coatings. *Surface and Coatings Technology*, **2000**, 125, 322-330	4.4	863
150	A study on the synthesis and microstructure of WCTiN superlattice coating. *Surface and Coatings Technology*, **2000**, 131, 372-377	4.4	26
149	Effect of Ti interlayer and bias on structure and properties of TiN films. *European Physical Journal D*, **2000**, 50, 655-663		3
148	Low pressure radio frequency and microwave discharges for d.c. sputtering of ferromagnetic materials. *European Physical Journal D*, **2000**, 50, 785-794		1
147	Microwave plasma nitriding of a low-alloy steel. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2000**, 18, 2715-2721	2.9	14

146	RECENT PROGRESS IN HARD NANOCOMPOSITE COATINGS. *High Temperature Material Processes*, **2000**, 4, 10	1.8	2
145	Rectangular magnetron with full target erosion. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **1999**, 17, 555-563	2.9	15
144	Structure and microhardness of magnetron sputtered ZrCu and ZrCu-N films. *Vacuum*, **1999**, 52, 269-275	3.7	38
143	Plasma nitriding enhanced by hollow cathode discharge – a new method for formation of superhard nanocomposite coatings on steel surfaces. *Vacuum*, **1999**, 55, 171-175	3.7	21
142	A perspective of magnetron sputtering in surface engineering. *Surface and Coatings Technology*, **1999**, 112, 162-169	4.4	39
141	Nanocrystalline and nanocomposite CrCu and CrCuN films prepared by magnetron sputtering. *Surface and Coatings Technology*, **1999**, 115, 32-37	4.4	69
140	CNxHy films obtained by ECR plasma activated CVD: the role of substrate bias (DC, RF) and some other deposition parameters in growth mechanisms. *Surface and Coatings Technology*, **1999**, 116-119, 65-73	4.4	5
139	ZrN/Cu nanocomposite film – a novel superhard material. *Surface and Coatings Technology*, **1999**, 120-121, 179-183	4.4	178
138	Microstructure and properties of nanocomposite TiBN and TiBC coatings. *Surface and Coatings Technology*, **1999**, 120-121, 405-411	4.4	158
137	Formation of Ti1−x Si x and Ti1−x Si x N films by magnetron co-sputtering. *European Physical Journal D*, **1999**, 49, 359-372		15
136	Magnetron sputtering of alloy and alloy-based films. *Thin Solid Films*, **1999**, 343-344, 47-50	2.2	47
135	Studies on Magnetron Sputtering Assisted by Inductively Coupled RF Plasma for Enhanced Metal Ionization. *Japanese Journal of Applied Physics*, **1999**, 38, 4291-4295	1.4	37
134	Magnetron sputtering of alloy-based films and its specifity. *European Physical Journal D*, **1998**, 48, 1209-1224		16
133	Nanocrystalline titanium carbide thin films deposited by reactive magnetron sputtering. *European Physical Journal D*, **1998**, 48, 963-971		3
132	Phase transformation in sputtered TiBS alloy film during plasma nitriding. *Thin Solid Films*, **1998**, 317, 458-462	2.2	0
131	Magnetron sputtering of films with controlled texture and grain size. *Materials Chemistry and Physics*, **1998**, 54, 116-122	4.4	99
130	Low-pressure magnetron sputtering. *Vacuum*, **1998**, 50, 363-372	3.7	92
129	Fundamentals of elementary processes in plasmas. *Surface and Coatings Technology*, **1998**, 98, 1557-1564	4.4	1

128	Recent advances in magnetron sputtering technology. *Surface and Coatings Technology*, **1998**, 100-101, 280-286	4.4	48
127	Composite TiN/Ni thin films deposited by reactive magnetron sputter ion-plating. *Surface and Coatings Technology*, **1998**, 110, 168-172	4.4	65
126	Formation of nanocrystalline NiCrN films by reactive dc magnetron sputtering. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **1998**, 16, 3301-3304	2.9	45
125	Inductively-Coupled-Plasma-Assisted Planar Magnetron Discharge for Enhanced Ionization of Sputtered Atoms. *Japanese Journal of Applied Physics*, **1997**, 36, 4568-4571	1.4	18
124	A comparison of internal plasma parameters in a conventional planar magnetron and a magnetron with additional plasma confinement. *Plasma Sources Science and Technology*, **1997**, 6, 46-52	3.5	22
123	Plasma nitriding combined with a hollow cathode discharge sputtering at high pressures. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **1997**, 15, 2636-2643	2.9	13
122	Planar magnetron sputtering discharge enhanced with radio frequency or microwave magnetoactive plasma. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **1997**, 15, 1999-2006	2.9	19
121	The structure of Cu-Al films prepared by unbalanced DC magnetron sputtering. *Surface and Coatings Technology*, **1997**, 96, 359-363	4.4	7
120	Study of UV Laser Ablation of Nitrided Steels Using Inductively Coupled Plasma Atomic Emission Spectrometry. *Collection of Czechoslovak Chemical Communications*, **1996**, 61, 1167-1176		3
119	Microwave plasma enhanced low pressure d.c. sputtering of copper films. *European Physical Journal D*, **1996**, 46, 353-368		4
118	Depth profile analysis of minor elements by GD-OES: Applications to diffusion phenomena. *FreseniuskJournal of Analytical Chemistry*, **1996**, 354, 188-192		3
117	Interdiffusion between Ti and steel elements in Ti coating/steel substrate couple. *Vacuum*, **1996**, 47, 871-877	3.7	2
116	Deposition of thin films using microwave plasmas: present status and trends. *Vacuum*, **1996**, 47, 145-155	3.7	23
115	XRD Characterization of thin films with low intensity reflection lines. *Vacuum*, **1996**, 47, 1145-1147	3.7	3
114	Low pressure magnetron sputtering and selfsputtering discharges. *Vacuum*, **1996**, 47, 307-311	3.7	41
113	Formation of high temperature phases in sputter deposited Ti-based films below 100 °C. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **1996**, 14, 2247-2250	2.9	27
112	High-rate magnetron sputtering. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **1996**, 14, 2187-2191	2.9	39
111	Discharge characteristics of a facing target sputtering device using unbalanced magnetrons. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **1996**, 14, 2182-2186	2.9	9

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